



<b>Session Title:</b>	<b>[WeF1] Nano Thin Film Deposition III</b>
<b>Session Date:</b>	<b>November 13 (Wed.), 2024</b>
<b>Session Time:</b>	<b>09:00-10:40</b>
<b>Session Room:</b>	<b>Room F (Ballroom, 5F, Grand Josun Busan)</b>
<b>Session Chair:</b>	<b>Prof. Jeong Hwan Han (Seoul Nat'l Univ. of Science and Tech., Korea)</b>

**[WeF1-1] [Invited] 09:00-09:30**

**Growth Inhibition of ZnS ALD by Atomic Layer Etching for Area Selective Deposition**

Taewook Nam (Sejong Univ., Korea) and Steven M. George (Univ. of Colorado Boulder, USA)

**[WeF1-2] [Invited] 09:30-09:55**

**Atomic Layer Deposition Process and Its Application for Semiconductor Field**

Woo-Jae Lee (Pukyong Nat'l Univ., Korea)

**[WeF1-3] [Invited] 09:55-10:20**

**Atomic-Layer-Deposition for the Advanced Technology**

Van Quang Nguyen, Jae Bin Ahn, Jongho Kim, Kang Hun Cho, and Jihye Kim (ISAC Research Inc., Korea)

**[WeF1-4] 10:20-10:40**

**A New Plasma Source for ALD Process in Large Batch System**

Jeonghee Jo, Kwanghyun Jin, Wooduck Jung, and Junjin Hyon (EUGENETECH, Korea)